



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Christopher H. McCoy et al.
Serial No.: 10/714190
Filed: November 14, 2003
Title: SOFT LITHOGRAPHIC PROCESS FOR FABRICATING
INTEGRATED ITO ELECTRODE-LIQUID CRYSTAL ALIGNMENT
LAYERS
Examiner: Joseph Williams
Art Unit: 2879

Mail Stop Patent Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

RESPONSE

This Response is in reply to the Office Action dated July 21, 2005. Applicants have amended claims 1 and 2 to overcome the Examiner's rejections under 35 U.S.C. §102 for anticipation based on U.S. Patent No. 6,156,433 to Hatori et al. ("Hatori") and U.S. Patent No. 5,507,404 to Ryu et al. ("Ryu"). Having overcome the Examiner's rejections to these claims, Applicants submit that these claims are in condition for allowance.

Applicants have also added new claims 3-20. These claims have features that distinguish them from Hatori and Ryu. Therefore, these claims are also in condition for allowance.

The amendments to the specification begin on page 2, the amendments to the claims begin on page 6 and the Remarks begin on page 10.